AMENDMENTS TO THE CLAIMS

This listing of claims replaces all prior versions, and listings, of claims in the application.

- 1-15. (Canceled).
- 16. (Currently Amended) A heat-sensitive lithographic printing plate precursor according to claim 15, wherein said coating further comprises a dissolution inhibitor comprising a support having a hydrophilic surface and an oleophilic coating provided on the hydrophilic surface, said coating comprising (i) an infrared light absorbing agent, (ii) a polymer comprising a phenolic monomeric unit wherein the phenyl group of the phenolic monomeric unit is substituted by a group having the structure -S-(L)_k-Q wherein S is covalently bound to a carbon atom of the phenyl group, wherein L is a linking group, k is 0 or 1 and Q comprises a heterocyclic group, and (iii) a dissolution inhibitor, and wherein said precursor is a positive working lithographic printing plate precursor.
- 17. (Previously Presented) A heat-sensitive lithographic printing plate precursor according to claim 16, wherein said dissolution inhibitor is selected from the group consisting of

an organic compound which comprises at least one aromatic group and a hydrogen bonding site,

a polymer or surfactant comprising siloxane orperfluoroalkyl units and mixtures thereof.

- 18-20. (Canceled).
- 21. (Currently Amended) A polymer precursor according to claim 2 claim 16 wherein said heterocyclic group contains at least one nitrogen atom in the ring of the heterocyclic group.
- 22. (Currently Amended) A polymer precursor according to elaim 2 claim 16 wherein said heterocyclic group has a 5- or 6- membered ring structure, and is optionally annelated with another ring system.

- 23. (Currently Amended) A polymer precursor according to claim 3 claim 21 wherein said heterocyclic group has a 5- or 6- membered ring structure, and is optionally annelated with another ring system.
- 24. (Currently Amended) A polymer precursor according to elaim 3 claim 16 wherein said heterocyclic group has a 5- or 6- membered ring structure, and is annelated with another ring system.
- 25. (Currently Amended) A polymer precursor according to elaim 24 claim 16 wherein the heterocyclic group is selected from an optionally substituted tetrazole, triazole, thiadiazole, oxadiazole, imidazole, benzimidazole, thiazole, benzthiazole, oxazole, benzoxazole, pyrrole, pyrimidine, pyrasine, pyridasine, triazine or pyridine group.
- 26. (Currently Amended) A polymer precursor according to elaim 5 claim 16, wherein said polymer comprising a phenolic monomeric unit is a novolac, resol or polyvinylphenol.
 - 27. (Canceled).
- 28. (Currently Amended) A heat-sensitive lithographic printing plate precursor according to elaim 15 claim 16 wherein -S-(L) k-Q comprises the following formula

wherein Z represents the necessary atoms to form a 5- or 6- membered heterocyclic aromatic group, and is optionally annelated with another ring system.

29. (Previously Presented) A heat-sensitive lithographic printing plate precursor according to claim 28 wherein the -S-(L)_k-Q comprises the following formula

wherein R¹ is selected from hydrogen or an optionally substituted alkyl, alkenyl, alkynyl, cycloalkyl, heterocyclic, aryl, heteroaryl, aralkyl or heteroaralkyl group.

30. (Currently Amended) A heat-sensitive lithographic printing plate precursor according to claim 28 wherein -S-(L)_k-Q comprises the following formula

$$--s-(L) = \begin{bmatrix} N & N \\ N & N \end{bmatrix}$$

wherein n is 0, 1, 2, 3, 4 or 5, wherein each R^1 is independently selected from hydrogen, an optionally substituted alkyl, alkenyl, alkynyl, cycloalkyl, heterocyclic, aryl, heteroaryl, aralkyl or heteroaralkyl group, halogen, [[-S0₂-NH-R,-NH-S0₂-R,]] -SO₂-NH-R, -NH-SO₂-R,-CO-NR-R,-NR-CO-R, -NR²-CO-NR³-R⁴, -NR²-CS-NR³-R⁴, -NR²-CO-O-R³, -O-CO-NR²-R³, -O-CO-R⁵, -CO-O-R², -CO-R², -SO₃-R², -O-SO₂-R⁵, -SO²-R², -SO-R⁵, -P(=O)(-O-R²)(-O-R³), -O-P(=O)(-O-R²)(-O-R³), -NR²-R³, -O-R², -S-R², -CN, -NO₂ or -M-R², wherein M represents a divalent linking group containing 1 to 8 carbon atoms, where in R² to R⁴ are independently selected from hydrogen or an optionally substituted alkyl, alkenyl, alkynyl, cycloalkyl, heterocyclic, aryl, heteroaryl, aralkyl or heteroaralkyl group, wherein R⁵ is an optionally substituted alkyl, alkenyl, alknyl, cycloalkyl, heterocyclic, aryl, heteroaryl, aralkyl or heteroaralkyl group, or wherein at least two groups selected from each R¹, R², R³, R⁴ and R⁵ together represent the necessary atoms to form a cyclic structure.

31. (Currently Amended) A heat-sensitive lithographic printing plate precursor according to claim 28 wherein -S-(L)_k-Q comprises the following formula

wherein X is [[0]] \underline{O} , S or NR³, wherein R is selected from hydrogen, an optionally substituted alkyl, alkenyl, alkynyl, cycloalkyl, heterocyclic, aryl, heteroaryl, aralkyl or heteroaralkyl group, halogen or -L¹-R², where in L¹ is a linking group, wherein R² is selected from hydrogen, an optionally substituted alkyl, alkenyl, alkynyl, cycloalkyl, heterocyclic,

aryl, heteroaryl, aralkyl or heteroaralkyl group, halogen or -CN, wherein R^3 is selected from hydrogen or an optionally substituted alkyl, alkenyl, alkynyl, cycloalkyl, heterocyclic, aryl, heteroaryl, aralkyl or heteroaralkyl group, or wherein at least two groups selected from R^1 , R^2 and R^3 represent the necessary atoms to form a cyclic structure.

32. (Currently Amended) A heat-sensitive lithographic printing plate precursor according to claim 28 wherein -S-(L)_k-Q comprises the following formula

$$-s-(L) \underset{\mathbb{R}}{\longleftarrow} \mathbb{R}^1$$

wherein X is O, S or NR^4 , wherein R^1 and R^2 are independently selected from hydrogen, an optionally substituted alkyl, alkenyl, alkynyl, cycloalkyl, heterocyclic, aryl, heteroaryl, aralkyl or heteroaralkyl group, halogen or [[-L1-R3]] -L^1-R^3 wherein L^1 is a linking group, wherein R^3 is selected from hydrogen, an optionally substituted alkyl, alkenyl, alkynyl, cycloalkyl, heterocyclic, aryl, heteroaryl, aralkyl or heteroaralkyl group, halogen or -CN, wherein R^4 is selected from hydrogen or an optionally substituted alkyl, alkenyl, alkynyl, cycloalkyl, heterocyclic, aryl, heteroaryl, aralkyl or heteroaralkyl group, or wherein at least two groups selected from R^1 , R^2 , R^3 and R^4 together represent the necessary atoms to form a cyclic structure.

33. (Currently Amended) A heat-sensitive lithographic printing plate precursor according to claim 28 wherein -S-(L)_k-Q comprises the following formula

$$-s-(L) \frac{1}{k} \left[R^{2}\right]_{n}$$

wherein n is 0, 1, 2, 3 or 4, wherein X is O, S or NR⁵, wherein each R¹ is independently selected from hydrogen, an optionally substituted alkyl, alkenyl, alkynyl, cycloalkyl, heterocyclic, aryl, heteroaryl, aralkyl or heteroaralkyl group, halogen, -SO₂-NH-R², -NH-SO₂-R⁶, -CO-NR²-R³, -NR²-CO-R⁶, -NR²-CO-NR³-R⁴, -NR²-CS-NR³-R⁴, -NR²-CO-O-R³, -O-CO-NR²-R³, -O-CO-R⁶, -CO-O-R², -CO-R², -SO₃-R², -O-SO₂-R⁶, -SO₂-R², -SO-R⁶, [[-P(=o)(-O-R²)(-O-R³),]] -P(=O)(-O-R²)(-O-R³), -O-P(=O)(-O-R²)(-O-R³),

-NR²-R³, -O-R², -S-R², -CN, -NO₂ or -M-R², wherein M represents a divalent linking group containing 1 to 8 carbon atoms, wherein R² to R⁵ are independently selected from hydrogen or an optionally substituted alkyl, alkenyl, alkynyl, cycloalkyl, heterocyclic, aryl, heteroaryl, aralkyl or heteroaralkyl group, wherein R⁶ is an optionally substituted alkyl, alkenyl, alkynyl, cycloalkyl, heterocyclic, aryl, heteroaryl, aralkyl or heteroaralkyl group, or wherein at least two groups selected from each R¹, R², R³, R⁴, R⁵ and R⁶ represent the necessary atoms to form a cyclic structure.

34. (Previously Presented) A heat-sensitive lithographic printing plate precursor according to claim 28 wherein -S-(L)_k-Q comprises the following formula

$$-s - (L) = \sqrt{N - \left(\frac{1}{R^2} \right)_n}$$

wherein n is 0, 1, 2 or 3, wherein each R^1 is independently selected from hydrogen, an optionally substituted alkyl, alkenyl, alkynyl, cycloalkyl, heterocyclic, aryl, heteroaryl, aralkyl or heteroaralkyl group, halogen, $-SO_2-NR-R^2$, $-NR-SO_2-R^5$, $-CO-NR^2-R^3$, $-NR^2-CO-R^5$, $-NR^2-CO-NR^3-R^4$, $-NR^2-CS-NR^3-R^4$, $-NR^2-CO-O-R^3$, $-O-CO-NR^2-R^3$, $-O-CO-R^5$, $-CO-O-R^2$, $-CO-R^2$, $-SO_3-R^2$, $-O-SO_2-R^5$, $-SO_2-R^2$, $-SO-R^5$, $-P(=O)(-O-R^2)(-O-R^3)$, $-O-P(=O)(-O-R^2)(-O-R^3)$, $-NR^2-R^3$, $-O-R^2$, $-S-R^2$, -CN, $-NO_2$ or $-M-R^2$, wherein M represents a divalent linking group containing 1 to 8 carbon atoms, wherein R^2 to R^4 are independently selected from hydrogen or an optionally substituted alkyl, alkenyl, alkynyl, cycloalkyl, heterocyclic, aryl, heteroaryl, aralkyl or heteroaralkyl group, wherein R^5 is an optionally substituted alkyl, alkenyl, alkynyl, cycloalkyl, heterocyclic, aryl, heteroaryl, aralkyl or heteroaralkyl group, or wherein at least two groups selected from each R^1 , R^2 , R^3 , R^4 and R^5 together represent the necessary atoms to form a cyclic structure.

35-37. (Canceled).

38. (New) A precursor according to claim 16, wherein said polymer comprising a phenolic monomeric unit is a novolac.